



Patent

Attorney's Docket No. 015290-426

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Patent Application of ) **BOX AF**  
)  
William Frederick BOSCH ) Group Art Unit: 1765  
)  
Application No.: 09/607,922 ) Examiner: L. T. Umez-Eronini  
)  
Filed: June 30, 2000 )  
)  
For: SEMICONDUCTOR PROCESSING )  
EQUIPMENT HAVING IMPROVED )  
PARTICLE PERFORMANCE )

**RECEIVED**  
APR 24 2002  
**TC 1700**

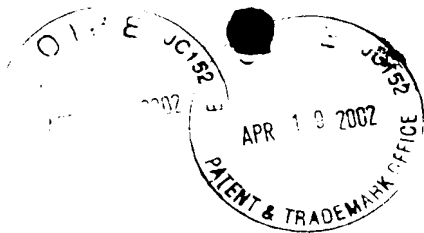
**AMENDMENT/REPLY TRANSMITTAL LETTER**

Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

Enclosed is a reply for the above-identified patent application.

- ☐ A Petition for Extension of Time is also enclosed.
- ☐ A Terminal Disclaimer and a check for ☐ \$55.00 (248) ☐ \$110.00 (148) to cover the requisite Government fee are also enclosed.
- ☒ Also enclosed is an Information Disclosure Statement.
- ☐ Small entity status is hereby claimed.
- ☐ Applicant(s) request continued examination under 37 C.F.R. § 1.114 and enclose the ☐ \$370.00 (279) ☐ \$740.00 (179) fee due under 37 C.F.R. § 1.17(e).
  - ☐ Applicant(s) previously submitted \_\_, on \_\_, for which continued examination is requested.
- ☐ Applicant(s) request suspension of action by the Office until at least \_\_, which does not exceed three months from the filing of this RCE, in accordance with 37 C.F.R. § 1.103(c). The required fee under 37 C.F.R. § 1.17(i) is enclosed.
- ☐ A Request for Entry and Consideration of Submission under 37 C.F.R. § 1.129(a) (146/246) is also enclosed.
- ☐ No additional claim fee is required.



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7/13/02  
4/15/02

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**AMENDMENT AFTER FINAL REJECTION**

Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

In response to the Official Action mailed March 5, 2002, please amend the above-identified application as follows.

**IN THE CLAIMS:**

Please replace Claims 1, 15-18 and 24-29 and add new Claims 31-34 as follows:

1. (Amended) A method of processing semiconductor substrates and reducing particle contamination during processing of the substrates, the method comprising steps of:
- (a) placing at least one substrate on a substrate holder in an interior space of a vacuum processing chamber, the processing chamber including at least one ceramic part made of a non-oxide ceramic material and having a machined and/or sintered surface exposed to the interior space, the exposed surface having been treated to reduce particles of